

- fied pulse laser beam comprised of laser pulses having durations of less than 1 ns and power levels of more than 100×10^6 Watts with and average beam power in excess of 3 Watts and defining an amplified beam path,
- E) a focusing means for focusing on a target said amplified pulse laser beam to a spots smaller in cross section than 100×10^{-6} cm² to produce pulse intensity levels in excess of 10^{12} Watts/cm².
2. A laser system as in claim 1 and further comprising a multiplexing means for increasing the preamplified pulse rate in said preamplified pulse laser beam.
3. A laser system as in claim 1 wherein said preamplifier is a multi-pass laser amplifier said system further comprising a spatial filter means for spatially filtering said seed beam after its first pass through said first pass through said preamplifier.
4. A laser system as in claim 1 wherein said laser amplifier is a multi-pass laser amplifier.
5. A laser system as in claim 1 wherein said seed laser means comprises a Nd:YAG laser oscillator, a dye laser with a cavity dumper and a frequency doubler.
6. A laser system as in claim 5 wherein said small excimer laser is created within said first laser amplifier.
7. A laser system as in claim 1 wherein said seed laser means comprises a small excimer laser defining a small laser output and a Pockels cell configured to slice a pulse of less than 100 picoseconds from said small laser output.
8. A laser system as in claim 1 wherein said seed laser means comprises a mode-locked, q-switched Cr:LISAF laser.
9. A laser system as in claim 1 wherein said laser system further comprises a saturable absorber dye positioned in said amplifier beam path.

10. An improved high average power, high brightness laser system comprising:

- A) at least one seed laser means for producing a seed laser beam consisting of a series of pulses each pulse having a duration of less than 1 ns with a pulse rate in excess of 100 pulses per second,
- B) at least one XeCl excimer preamplifier arranged to amplify said seed laser beam to produce a preamplified pulse laser beam defining a preamplified pulse rate,
- C) at least one multiplex means for increasing the preamplified pulse rate in said preamplified pulse laser beam,
- D) at least one XeCl excimer laser amplifier arranged to amplify said preamplified laser beam to produce an amplified pulse laser beam comprised of laser pulses having durations of less than 1 ns and power levels of more than 100×10^6 Watts with and average beam power in excess of 3 Watts and defining an amplified beam path,
- E) at least one focusing means for focusing on a target said at least one amplified pulse laser beam to spots smaller in cross section than 100×10^{-6} cm² to produce pulse intensity levels in excess of 10^{12} Watts/cm.
11. A laser system as in claim 10 wherein said at least one XeCl excimer laser amplifier is a plurality of XeCl laser amplifiers being arranged to operate in a parallel configuration.

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